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ning of each regular issue of the PCT Gazette.

(54) Title: POLISHING PAD CONTAINING INTERPENETRATING LIQUIFIED VINYL MONOMER NETWORK WITH
POLYURETHANE MATRIX THEREIN

(57) Abstract: Provided is a polyurethane polishing pad. More specifically, the present invention provides a polyurethane polishing
pad having an interpenetrating network structure of a vinyl polymer with a polyurethane matrix via radical polymerization and having
no pores and gas bubbles. The polyurethane polishing pad having an interpenetrating network structure of a vinyl polymer exhibits
uniform dispersibility and reduced changes in hardness of the urethane pad due to heat and slurry, thereby resulting in no deterioration
of polishing efficiency due to abrasion heat and solubility in the slurry upon polishing, and also enables a high-temperature polishing
operation. Further, according to the present invention, the interpenetrating network structure leads to an improved polishing rate and
abrasion performance, thereby significantly increasing the service life of the polishing pad.



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